# Reactive Magnetron Sputter System

## Model: SA-VKV550

SA-VKV550 is an ion-source-enhanced reactive magnetron sputtering system. It delivers superior film quality, features a highly automated control system and low-maintenance design, and satisfies R&D and small-batch-production requirements for enterprises and research institutes.




## Feature

- High thin-film purity
- Excellent substrate adhesion
- Relatively high ionization rate
- Co-sputtering with mixed targets

## Application

- Laser
- R&D
- Intergated circuit
- MEMS

## Specifications：

| Parameter | Descriptions |
|---|---|
| Number of Cathodes | 2(max.) |
| Sputtering Power Supply | DC / RF / pulsed DC, freely switchable |
| Ion Source | RF & Kaufman & Hall ion source |
| Bias | RF / pulsed DC |
| Vacuum Sampling Chamber | Single-wafer/multi-wafer fully-automatic sampling chamber, optional |
| Pumping System | Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump |
| Flow Control | Digital mass flow meter |
| Coating Uniformity | ±2% |
| Coating Repeatability | ±2% |
| Uniform Deposition Area | Ø200 mm(max.) |
| Ultimate Vacuum | 1E-5Pa |
| Vacuum Measurement | Full-range vacuum gauge + Capacitance diaphragm gauge |
| Temperature Control Range | -50~800℃ |
| Space Requirements(L×W×H,m) | 3.8×2.8×2.2 |

## Principle：

